

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant:	Hong-Jyh Li et al.	Examiner:	Quoc Dinh Hoang
Serial No.:	10/799,910	Group Art Unit:	2818
Filed:	March 12, 2004	Docket No.:	I550.115.101/2004P50029US
Title:	ION IMPLANTATION OF HIGH-K MATERIALS IN SEMICONDUCTOR DEVICES		

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**AMENDMENT AND RESPONSE**

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

This Amendment and Response is in reply to the Non-Final Office Action mailed November 29, 2007. Please amend the above-identified patent application as follows: